

**AMENDMENTS TO THE CLAIMS**

Claims 1-16 (canceled)

17. (New) An apparatus for processing a substrate, the apparatus being formed by combining etching and stripping equipment with cleaning equipment, the etching and cleaning equipment being comprised of modules joined end to end to form a unified structure, wherein the substrate is moved directly out of one of the modules into another one of the modules in succession, the unified structure comprising:

an etching line comprising an etch module joined end to end with a rinse module for etching and rinsing the substrate prior to stripping;

a stripping line for stripping the substrate, the stripping line being connected to the etching line;

a transfer module having an end thereof directly joined to an end of the etching line and an end thereof directly joined to the stripping line, for moving the substrate from the etching line to the stripping line with no exposure of the substrate to the outside of said unified structure;

a cleaning line installed on the stripping line to clean and dry the substrate; and

an elevator for conveying the substrate from the stripping line to the cleaning line,

wherein, the unified structure is sequentially arranged in the order the etching line, the transfer module, the stripping line, the elevator and the cleaning line.

18. (New) The apparatus as claimed in claim 17, further comprising:

a loader for moving the substrate to the etching line; and

an unloader for receiving the substrate from the cleaning line.

19. (New) The apparatus as claimed in claim 18, wherein:

the etch module etches the substrate;

the substrate is moved from the etch module into the rinse module; and

the rinse module cleans the substrate.

20. (New) The apparatus as claimed in claim 17, wherein the stripping line and the cleaning line are stacked to have a two-tier structure.

21. (New) An apparatus for processing a substrate, the apparatus including etching, stripping and cleaning equipment forming a unified structure comprised of modules joined together end to end, such that the substrate is not exposed to the outside of any of the modules during processing, the unified structure comprising:

an etching line comprising an etch module having an end thereof joined to a rinse module, for etching and cleaning the substrate;

a stripping line for stripping said substrate, said stripping line being unified with said etching line through a transfer module, wherein said transfer module moves the substrate from said etching line to said stripping line while preventing the substrate from drying;

a cleaning line integrated with said stripping line to clean and dry the substrate; and

an elevator to transfer said substrate from said stripping line to said cleaning line,

wherein, the unified structure is sequentially arranged in the order the etching line, the transfer module, the stripping line, the elevator and the cleaning line.

22. (New) The apparatus of claim 21, wherein said cleaning line is installed on said stripping line.

23. (New) The apparatus of claim 21, wherein the rinse module is connected to said etch module.

24. (New) The apparatus of claim 21, wherein said preventing the substrate from drying is accomplished by a pipe shower providing a fluid on the substrate.

25. (New) The apparatus as claimed in claim 21, wherein the stripping line and the cleaning line are stacked to have a two-tier structure.

26. (New) The apparatus of claim 21, further comprising:  
a loader for loading the substrate to the etching line; and  
an unloader for unloading the substrate from the cleaning line.

27. (New) The apparatus of claim 25, wherein said loader includes at least one of a conveyor and a robot.

28. (New) The apparatus of claim 25, wherein said unloader includes at least one of a conveyor and a robot.